AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

Claims 1-11 (canceled).

Claim 12. (previously presented): A bottom anti-reflective coating material composition comprising a polymer light absorbent having at least one group represented by the following formula (X), (XII), (XIII), (XIV) or (XV) on the side chain and

a thermal cross-linking agent:

$$(X_1)(X_2)C = C$$
 $(Z_1)_n$
 $(X_1)(X_2)C = C$
 $(X_1)(X_2)C = C$

$$(X_3)(X_2)C = C(X_1)$$

$$(Z_2)_m \qquad W' \qquad (XI)$$

$$(X_3)(X_2)C = C(X_1)$$

$$-W' \qquad (Z_1)_n \qquad (XII)$$

$$-\mathbf{W}'-\mathbf{A}_1$$
 $(\mathbf{Z}_2)_{\mathbf{m}}$
 $(\mathbf{Z}_{1})_{\mathbf{n}}$
 $(\mathbf{Z}_{2})_{\mathbf{m}}$

$$-\mathbf{W}'$$
 $(\mathbf{Z}_2)_{\mathbf{m}}$
 $(\mathbf{Z}_2)_{\mathbf{m}}$
 $(\mathbf{X}_1)_{\mathbf{N}}$

$$\begin{array}{c} -W' \\ A_2 \\ (Z_2)_m \end{array}$$

wherein W' represents a divalent linking group, X_1 to X_3 , which may be the same or different, each represents a hydrogen atom, a halogen atom, a cyano group or $-(X_4)_p$ -R wherein R represents an alkyl group having from 1 to 20 carbon atoms, an aryl group having from 6 to 20 carbon atoms or an aralkyl group having from 7 to 20 carbon atoms, which may have a

substituent, X_4 represents a single bond, $-CO_2$ -, -CONH-, -O-, -CO-, an alkylene group having from 2 to 4 carbon atoms or $-SO_2$ -, p represents an integer of from 1 to 10, Z_1 and Z_2 , which may be the same or different, each represents an electron donating group, m and n represent an integer of from 0 to 2 and from 0 to 3, respectively, and when m is 2 or m and n each is 2 or 3, the Z_1 groups or the Z_2 groups may be the same or different, A_1 represents a divalent aromatic ring or heteroaromatic ring group having from 5 to 14 carbon atoms, which may have a substituent, and A_2 represents an aromatic ring or heteroaromatic ring group having from 5 to 14 carbon atoms, which may have a substituent.

Claim 13 (canceled).

Claim 14 (previously presented). A bottom anti-reflective coating material composition comprising:

a polymer light absorbent having at least one repeating structural unit represented by the following formula (XXIV), (XXV) or (XXVI) and

a thermal cross-linking agent:

$$C(X_2) = C(X_1)$$

$$C(X_2) = C(X_1)$$

$$(Z_2)_m$$

$$(XXIV)$$

$$(X_1)(X_2)C = C$$

$$(Z_2)_m$$

$$(XX_1)(X_2)C = C$$

$$(XX_1)(X_2)C = C$$

$$(XX_1)(X_2)C = C$$

$$-(CH_{2}-C)$$

$$Y'$$

$$(Z_{2})_{m}$$

$$(XXVI)$$

wherein R¹ represents a hydrogen atom, a methyl group, a chlorine atom, a bromine atom or a cyano group, Y' in Formulae (XXV) and (XXVI) represents a divalent linking group and Y' in Formulae (XXIV) represents a -CO₂-E-, -CONH-E-, -O-E-, -CO-E- or -SO₂-E- group, wherein E

represents an aromatic ring group having from 6 to 14 carbon atoms, X_1 and X_2 , which may be the same or different, each represents a hydrogen atom, a halogen atom, a cyano group or $-(X_4)_p$ -R wherein R represents an alkyl group having from 1 to 20 carbon atoms, an aryl group having from 6 to 20 carbon atoms or an aralkyl group having from 7 to 20 carbon atoms, which may have a substituent, X_4 represents a single bond, $-CO_2$ -, -CONH-, -O-, -CO-, an alkylene group having from 2 to 4 carbon atoms or $-SO_2$ -, p represents an integer of from 1 to 10, Z_1 and Z_2 , which may be the same or different, each represents an electron donating group, m represents an integer of from 0 to 2, n represents an integer of from 0 to 3, and when m is 2 or m and n each is 2 or 3, the Z_1 groups or the Z_2 groups may be the same or different, A_1 represents a divalent aromatic ring or heteroaromatic ring group having from 5 to 14 carbon atoms, which may have a substituent.

Claim 15 (canceled).

Claim 16 (original): A bottom anti-reflective coating material composition as claimed in claim 12, wherein Z_1 and Z_2 , which may be the same or different, each represents -OH, -OR⁴, -NR⁵R⁶ or -SR⁴ wherein R⁴ represents a hydrocarbon group having from 1 to 20 carbon atoms, and R⁵ and R⁶ each represents a hydrogen atom or a hydrocarbon group having from 1 to 20 carbon atoms.

Claim 17 (original): A bottom anti-reflective coating material composition as claimed in claim 12, wherein A₁ and A₂ each represents a divalent or monovalent group of benzene, naphthalene, anthracene, phenanthrene or thiopene ring, which may have a substituent.

Claim 18 (previously presented): A bottom anti-reflective coating material composition as claimed in claim 12, wherein said polymer light absorbent contains from 2 to 50 wt% of the repeating structural unit represented by the following formula (XXVII):

$$\begin{array}{c|c}
 & R_2 \\
\hline
 & CH_2 - C \\
\hline
 & B_1
\end{array}$$
(XXVII)

wherein R₂ represents a hydrogen atom, a methyl group, a chlorine atom, a bromine atom or a cyano group, and B₁ represents a group containing -CH₂OH, -CH₂OR⁷ or -CH₂OCOCH₃ at the terminal wherein R⁷ represents a hydrocarbon group having from 1 to 20 carbon atoms.

Claim 19 (currently amended): A bottom anti-reflective coating material composition comprising a polymer light absorbent having at least one group represented by the following formula (X), (XI), (XII), (XIII), (XIV) or (XV) on the side chain:

$$(X_1)(X_2)C = C$$

$$(Z_1)_n$$

$$(X)$$

$$(X_3)(X_2)C = C(X_1)$$

$$(X_1)$$

$$(X_2)_m$$

$$W'$$

$$(X_3)(X_2)C = C(X_1)$$

$$-W$$

$$(Z_2)_m$$

$$(XII)$$

$$-\mathbf{W'}-\mathbf{A_1}$$

$$(\mathbf{Z_2})_{\mathbf{m}}$$

$$(\mathbf{XIII})$$

$$-\mathbf{W}'$$

$$(Z_2)_m \qquad \mathbf{A}_2$$
(XIV)

$$\begin{array}{c} -w' \\ A_2 \\ (Z_2)_m \end{array}$$

wherein W' represents a divalent linking group, X_1 to X_3 , which may be the same or different, each represents a hydrogen atom, a halogen atom, a cyano group or $-(X_4)_p$ -R wherein R represents an alkyl group having from 1 to 20 carbon atoms, an aryl group having from 6 to 20 carbon atoms or an aralkyl group having from 7 to 20 carbon atoms, which may have a substituent, X_4 represents a single bond, $-CO_2$ -, -CONH-, -O-, -CO-, an alkylene group having from 2 to 4 carbon atoms or $-SO_2$ -, p represents an integer of from 1 to 10, Z_1 and Z_2 , which may be the same or different, each represents an electron donating group, m and n represent an integer of from 0 to 2 and from 0 to 3, respectively, and when m is 2 or m and n each is 2 or 3, the Z_1 groups or the Z_2 groups may be the same or different, A_1 represents a divalent aromatic ring or heteroaromatic ring group having from 5 to 14 carbon atoms, which may have a substituent, and A_2 represents an aromatic ring or heteroaromatic ring group having from 5 to 14 carbon atoms, which may have a substituent;

and having from 2 to 50 wt% of a repeating structural unit represented by formula (XXVII):

$$--\left(CH_2-C\right)$$

$$B_1$$
(XXVII)

where R₂ represents a hydrogen atom, a methyl group, a chlorine atom, a bromine atom or a cyano group, and B₁ represents -CONHCH₂OH, -CONHCH₂OCH₃, -CH₂OCOCH₃, -C₆H₃(OH)CH₂OH, C₆H₃(OH)CH₂OCH₃ or a group obtained by reaction of a group represented by -CONHC(CH₃)₂CH₂COCH₃ with formalin.

Claim 20 (canceled).

Claim 21 (original): A bottom anti-reflective coating material composition comprising the following components (a) and (b):

- (a) a polymer light absorbent claimed in claim 12; and
- (b) a melamine, guanamine, glycoluril or urea compound substituted by at least one substituent selected from a methylol group, an alkoxymethyl group and an acyloxmethyl group.

Claims 22-23 (canceled).

Claim 24 (previously presented): A method for forming a resist pattern comprising the steps of:

dissolving a bottom anti-reflective coating material composition of claim 12 in a solvent to provide a bottom anti-reflective coating solution;

coating the bottom anti-reflective coating solution on a substrate to form a bottom antireflective coating;

curing the coating;

coating a photoresist on the cured bottom anti-reflective coating;

imagewise-exposing the photoresist to light;

optionally subjecting the photoresist to post-exposure baking; and

developing, rinsing and drying the imagewise-exposed photoresist to form a resist pattern.